

RESPONSE UNDER 37 C.F.R. § 1.116  
EXPEDITING PROCEDURE  
EXAMINING GROUP 1700

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Wunnicke, *et al.* Docket No.: INF 2004 SP 00138 US  
Serial No.: 10/781,920 Art Unit: 1795  
Filed: February 20, 2004 Examiner: Brittany L. Raymond  
For: Method for Fabricating a Resist Mask for Patterning Semiconductor Substrates

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE UNDER 37 CFR § 1.116**

Dear Sir:

Applicant respectfully submits the following remarks in response to Examiner's Office Action dated January 2, 2008, which Action was made final. Applicant respectfully requests that these remarks be entered in pursuant to the provisions of 37 CFR § 1.116, and respectfully request reconsideration of the claims.